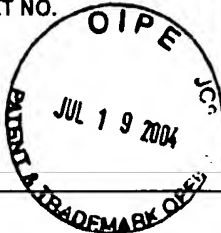



Form PTO 1449 <div style="text-align: center;"> <b>U.S. DEPARTMENT OF COMMERCE</b>  <b>PATENT AND TRADEMARK OFFICE</b> </div> <b>LIST OF REFERENCES CITED BY APPLICANT</b> (Use Several Sheets if Necessary)		ATTY. DOCKET NO. 55071-280		SERIAL NO. 10/662,365	
					
		APPLICANT J. Fung CHEN, et al.			
		FILING DATE September 1, 2003		GROUP 1756	



  

EXAMINER INITIAL	AA	DOCUMENT NUMBER	DATE	NAME	FILING DATE IF APPROPRIATE
		5,302,477	4/12/94	Dao et al.	
		5,348,826	9/20/94	Dao et al.	
		5,354,632	10/11/94	Dao et al.	
		5,384,219	1/24/95	Dao et al.	
		5,618,643	4/8/97	Dao et al.	
		5,633,102	5/27/97	Toh et al.	
		6,458,495	10/1/02	Tsai et al.	

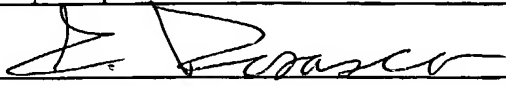
  

FOREIGN PATENT DOCUMENTS					
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO
	AL				
	AM				
	AN				
	AO				

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)		
	AR	Toh, et al., "Optical Lithography with Chromeless Phase-Shifted Masks", SPIE Vol. 1463, pp.74-86.
	AP	Levenson, et al., "SCAA Mask Exposures and Phase Phirst Design for 110nm and Below", Proc. SPIE Vol. 4346, pp.817-826.
	AS	Watanabe, et al., "Sub-quarter-Micron Gate Pattern Fabrication Using a Transparent Phase Shifting Mask", J. Vac. Sci. Technol, B, Vol. 9, No. 6, Nov/Dec 1991, pp. 3172-3175.
	AT	Watanabe, et al., "Transparent Phase Shifting Mask", IEDM 90, pp. 33.2.1 to 33.2.4.

EXAMINER 	DATE CONSIDERED <b>8/9/04</b>
--	-------------------------------

\*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.